OIPE JC184
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PATENT & TRADEMARK OFFICE

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Applicant:	Robert P. Meagley et al.	§	Art Unit:	1765
Serial No.:	10/679,793	§	Examiner:	Kin Chan Chen
Filed:	October 6, 2003	§	Atty Docket:	ITL.1018US P16705
For:	Increasing the Etch Resistance of Photoresists	§	Assignee:	Intel Corporation

Mail Stop **Amendment**
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO RESTRICTION REQUIREMENT

Sir:

In response to the restriction requirement mailed July 8, 2005, please amend the above-referenced patent application as follows:

Date of Deposit: July 14, 2005
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Cynthia L. Hayden

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